Feature

- ●Precision MEMS process
- ●High performance, shielded, Micro-cavity structure
- ●Silicon substrate, 50Ω CPW output
- ●Au wire bonding, for MCM applications

Environmental Specifications

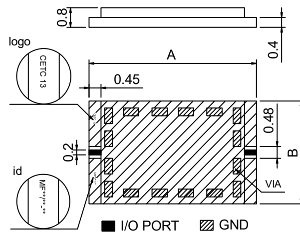
Operating Temperature	-55℃~+85℃
Storage Temperature	-55℃~+125℃
Max. Input Power	35dBm

Electrical Specifications(T_A=+25℃)

Parameter	Min.	Typ.	Max.	Unit
Center Freq. (f_0)	-	3.1	-	GHz
Pass Band	2.7	-	3.5	GHz
Ripple in Pass band	-	-	1	dB
Insertion Loss @ f_0	-	-	1.9	dB
Return Loss	15	-	-	dB
Out of band Attenuation	≥30@2.3GHz&3.9GHz			dB
	≥40@2.15GHz&4GHz			dB
	≥60@DC~1.7GHz			dB
	≥60@5~7.5GHz			dB
Group Delay Variation	≤1.0@2.7~3.5GHz			ns
Linear Phase	≤±12@2.7~3.5GHz			°

S2P file name: SiMF3R1_R8-7D2.s2p

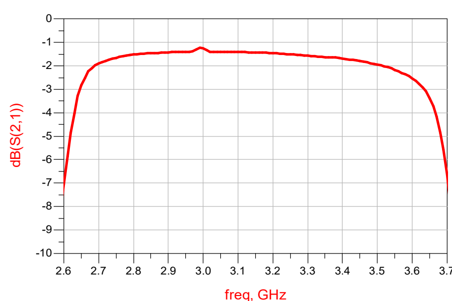
Outline Drawing



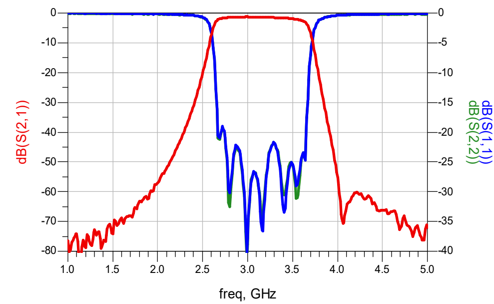
Symbol	Value (mm)		
	Min.	Nominal	Max.
A	6.9	-	7.0
B	8.9	-	9.0

Typical Test Curves

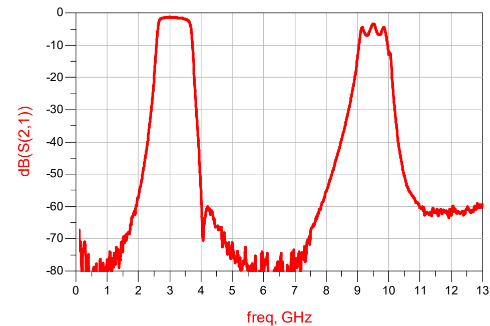
Insertion Loss VS Frequency (T_A=25℃)



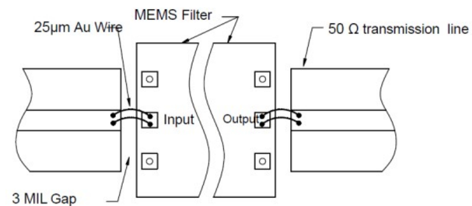
Insertion Loss & Return Loss VS Frequency (T_A=25℃)



Broadband Insertion Loss VS Frequency (T_A=25℃)

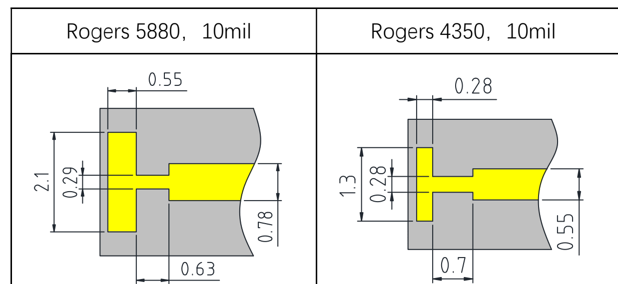


Recommended Assembly Diagrams



Application Notes:

1. The chip is back-metalized and can be die mounted with AuSn eutectic performs or with electrically conductive epoxy (for example ME8456).
2. The die should be assembled on carriers like Kovar or Mu-Cu which have same Coefficient of thermal expansion. (2.9ppm/℃) with Silicon, thickness 0.2mm max.
3. Handle the chips in a clean environment. DO NOT attempt to clean the chip using liquid cleaning systems.
4. Handle the chip along the edges with a vacuum collet or with a sharp pair of bent tweezers.
5. Recommended to use T structure as below for bonding.



6. If you have any questions, please contact us.